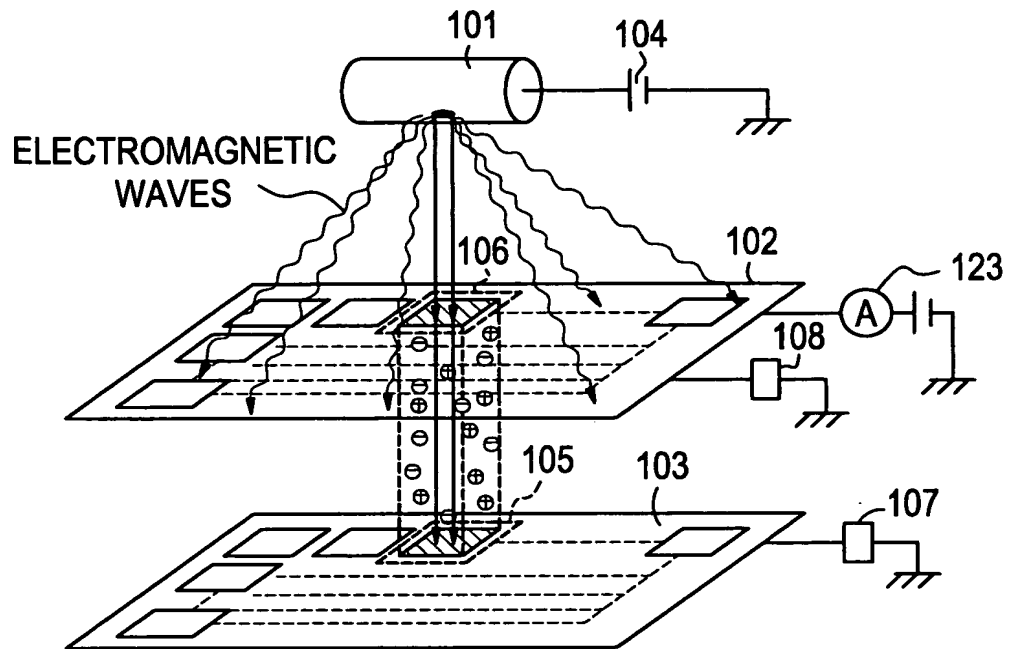
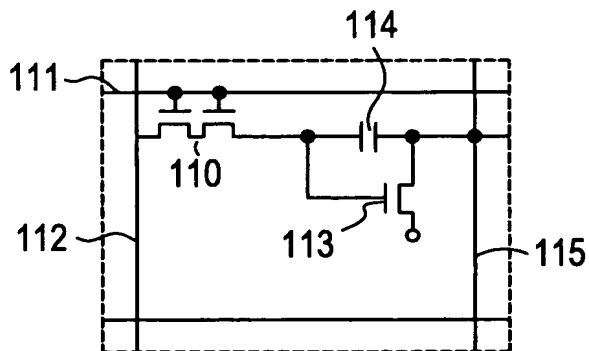


**FIG. 1A****FIG. 1B**

ENLARGED DIAGRAM OF 105

**FIG. 1C**

ENLARGED DIAGRAM OF 106

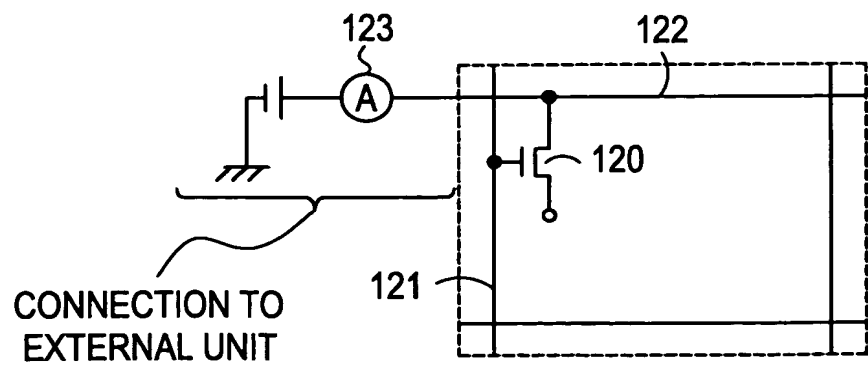


FIG. 2A

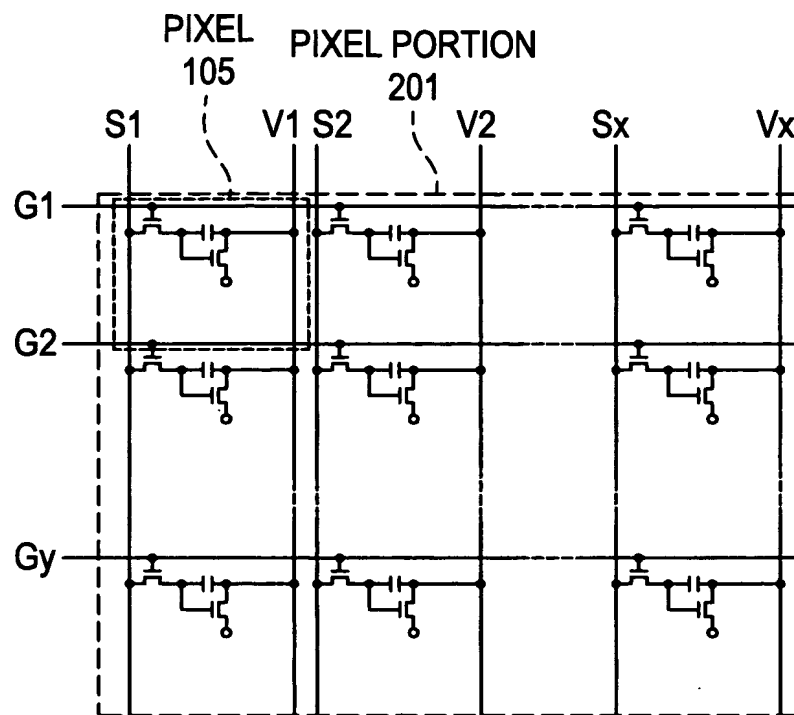


FIG. 2B

OPPOSING PORTION

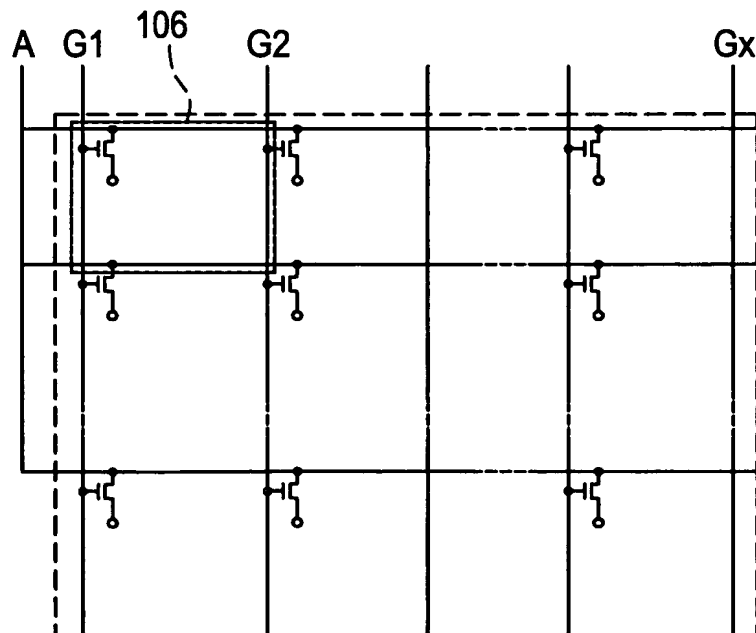
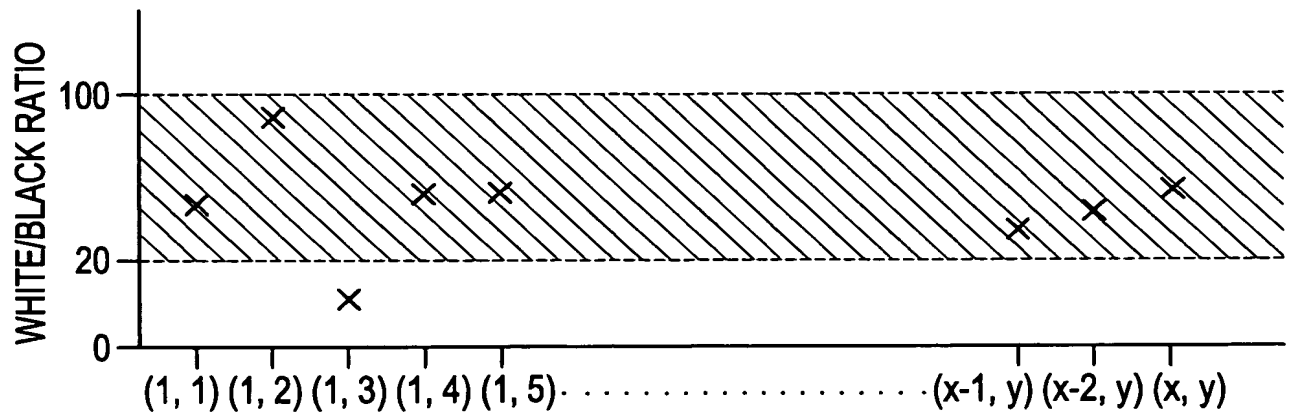


FIG. 3A

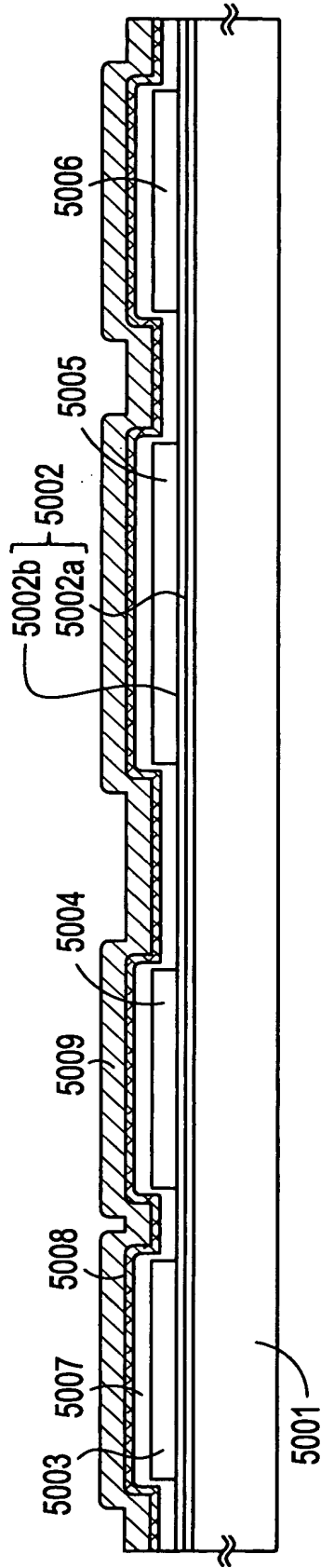
(1, 1)	(2, 1)	(3, 1)	(4, 1)		(x-1, 1)	(x, 1)
(1, 2)	(2, 2)	(3, 2)	(4, 2)		(x-1, 2)	(x, 2)
(1, 3)	(2, 3)	(3, 3)	(4, 3)		(x-1, 3)	(x, 3)
(1, 4)	(2, 4)	(3, 4)	(4, 4)		(x-1, 4)	(x, 4)
(1, y-1)	(2, y-1)	(3, y-1)	(4, y-1)		(x-1, y-1)	(x, y-1)
(1, y)	(2, y)	(3, y)	(4, y)		(x-1, y)	(x, y)

FIG. 3B



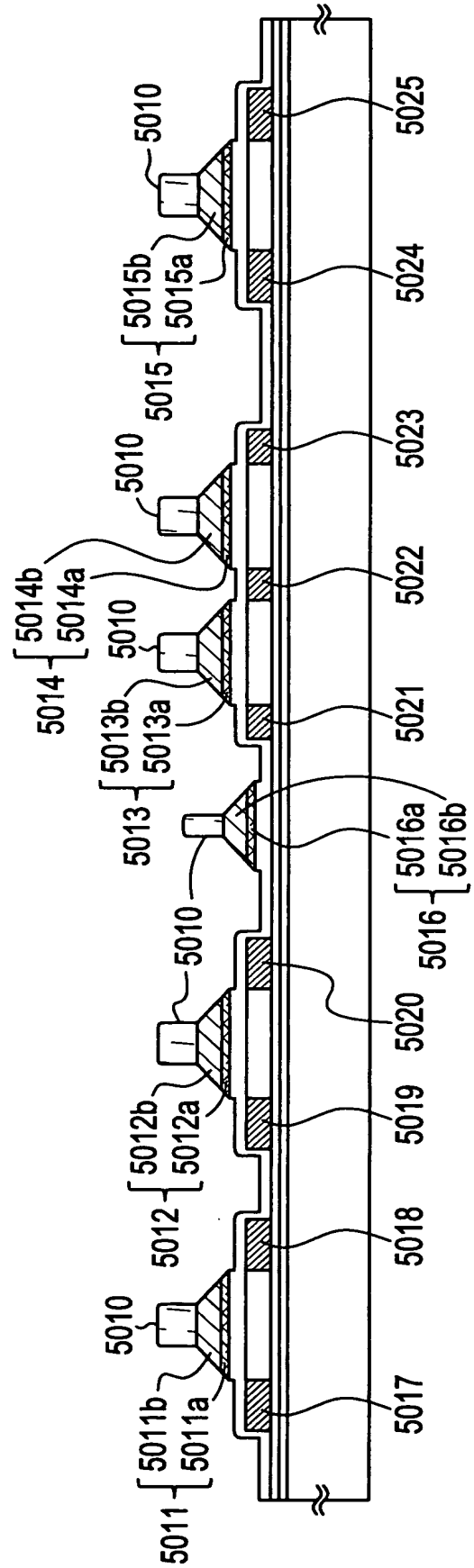
**FIG. 4A**

# FORMATION OF ISLAND SEMICONDUCTOR LAYER, GATE-INSULATING FILM, AND FIRST AND SECOND CONDUCTING FILMS FOR GATE ELECTRODES

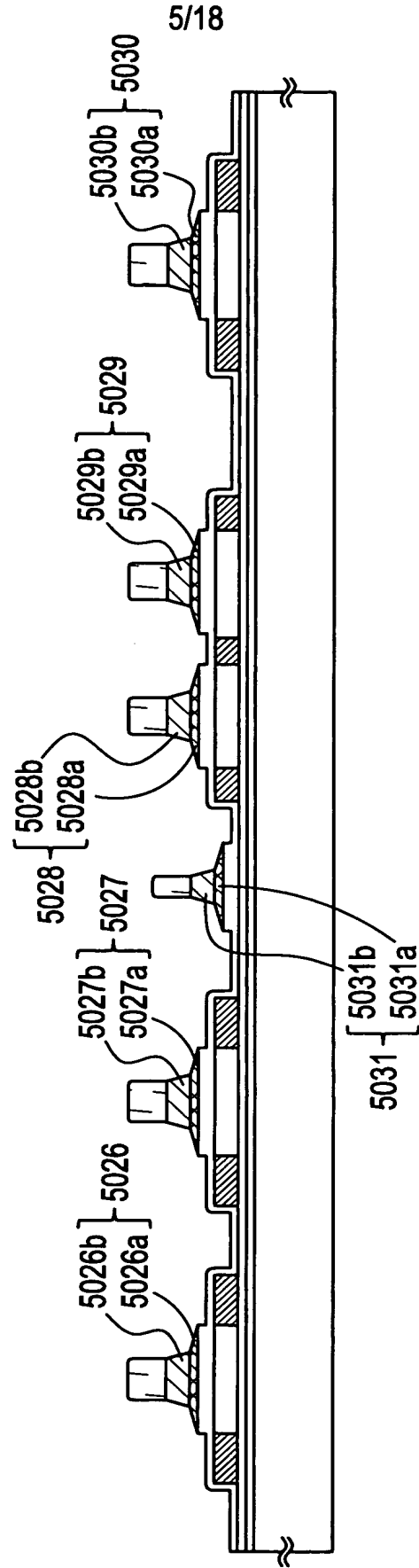


**FIG. 4B**

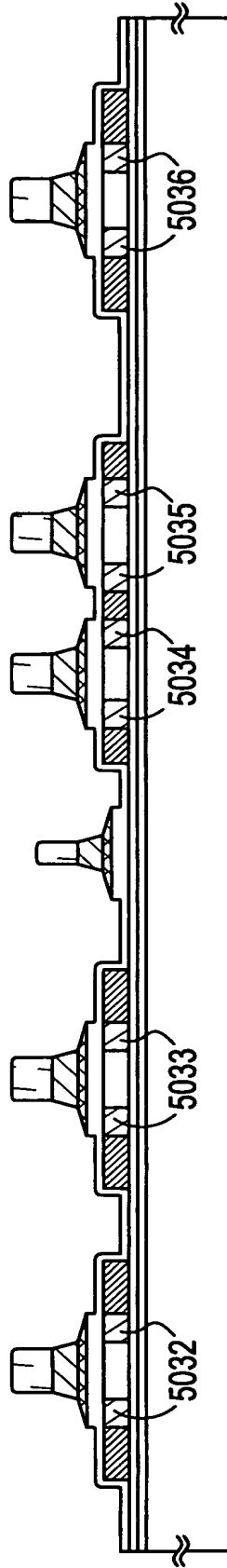
## FIRST ETCHING AND FIRST DOPING



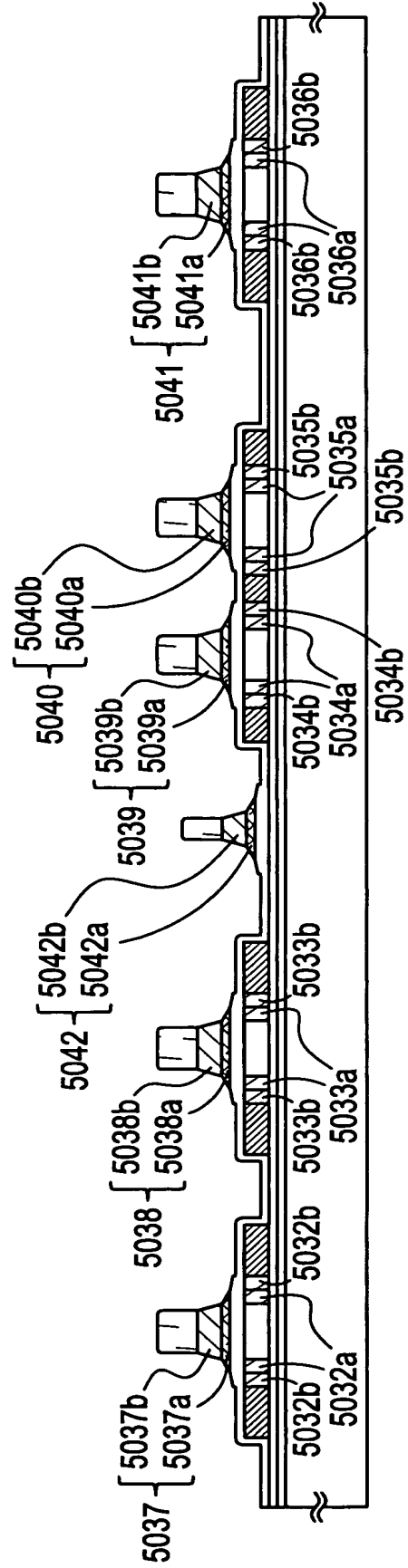
**FIG. 4C**  
SECOND ETCHING



**FIG. 5A**  
SECOND DOPING



**FIG. 5B**  
THIRD ETCHING



**FIG. 5C**  
THIRD DOPING

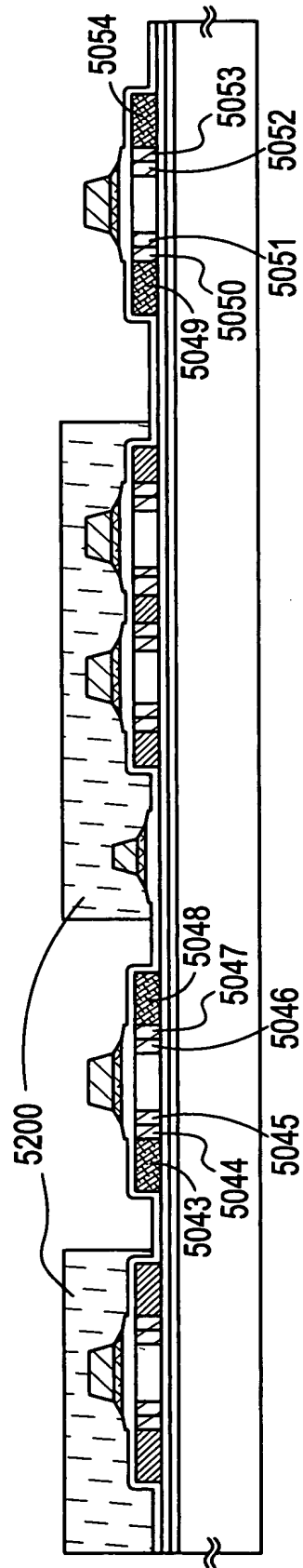


FIG. 6A

FORMATION OF THE FIRST AND SECOND INTERLAYER-INSULATING FILMS, WIRINGS AND PIXEL ELECTRODES

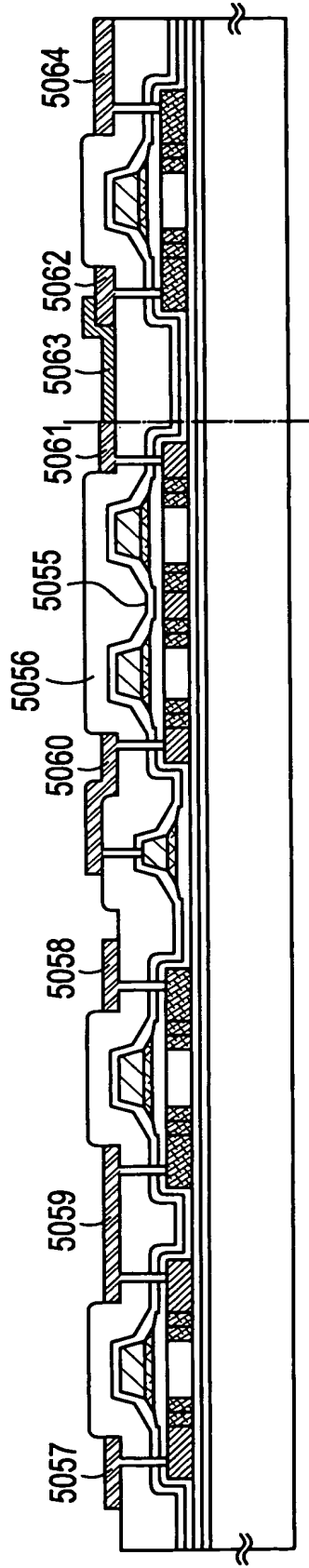
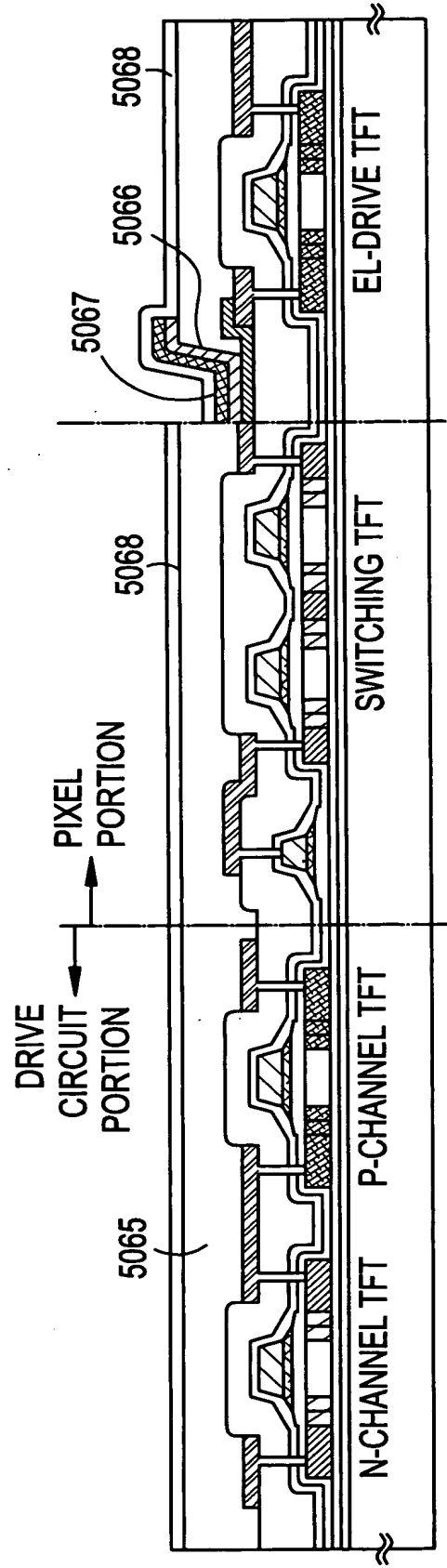


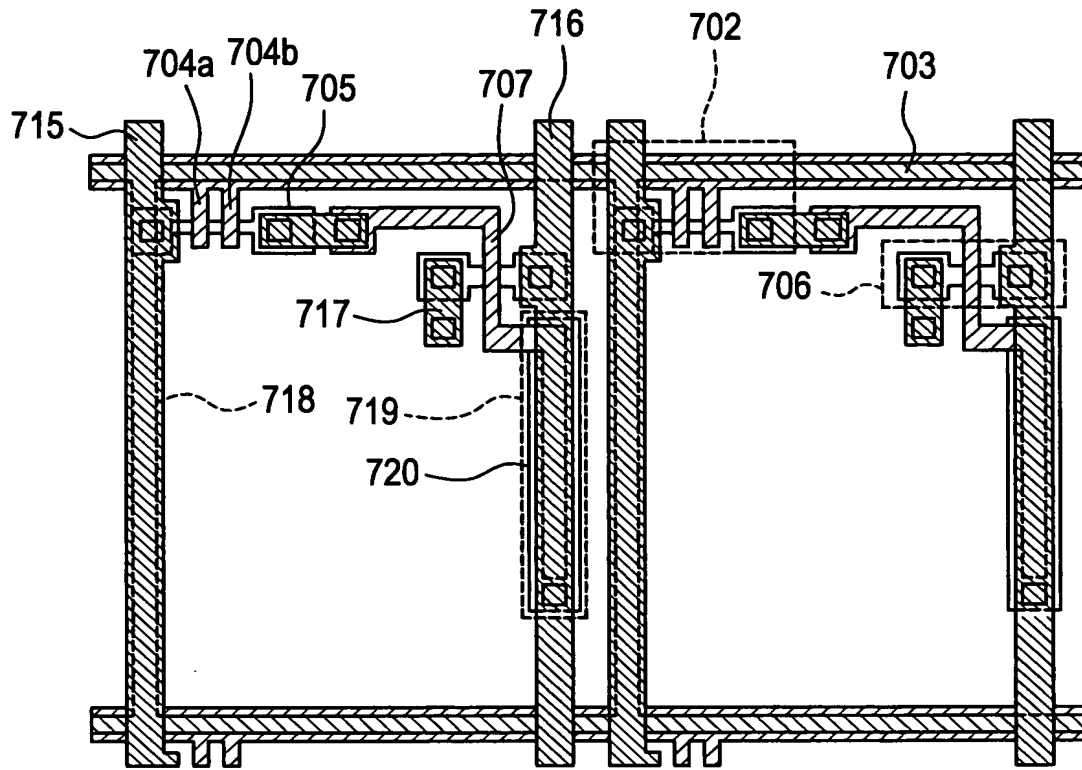
FIG. 6B

FORMATION OF THE THIRD INTERLAYER-INSULATING FILM, EL LAYER, CATHODES AND PASSIVATION FILM





**FIG. 7A**



**FIG. 7B**

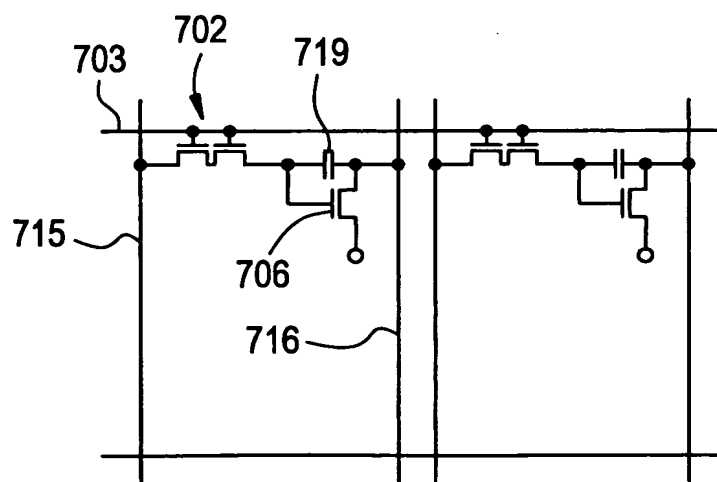


FIG. 8A

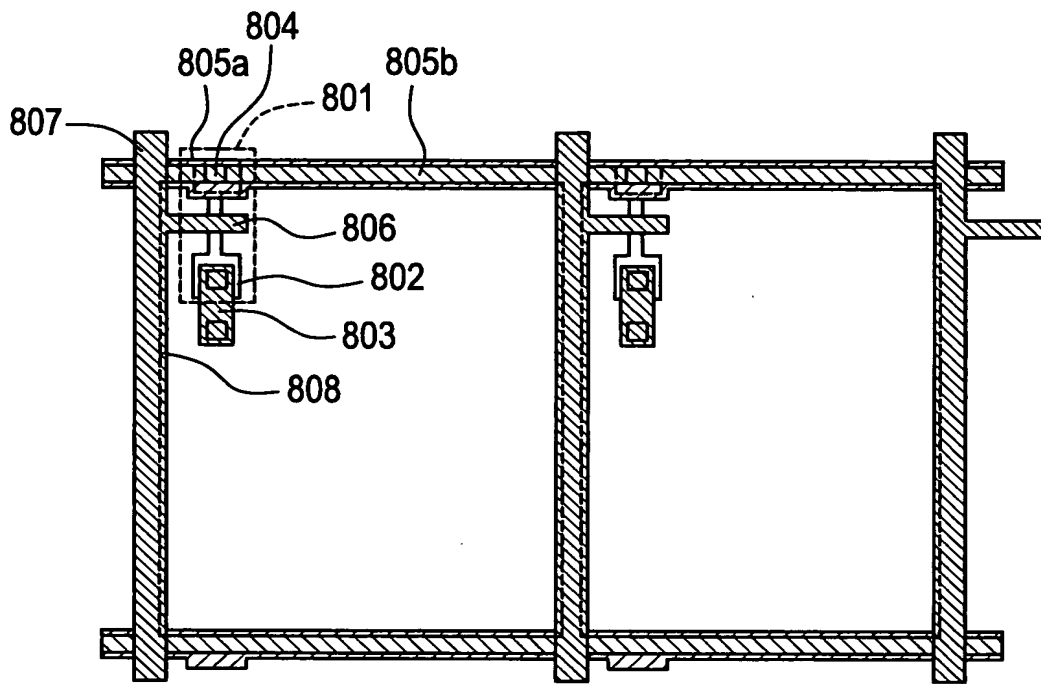


FIG. 8B

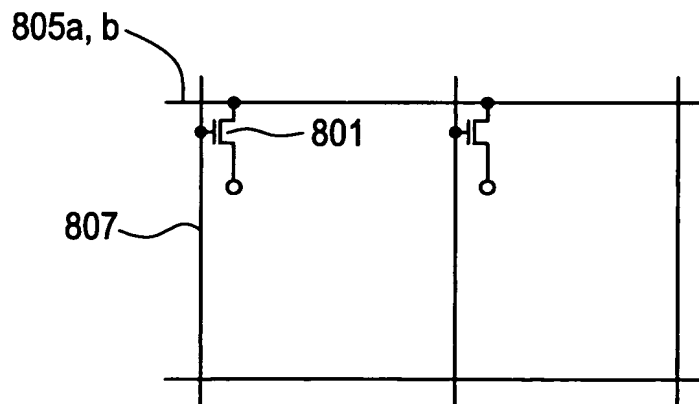


FIG. 9

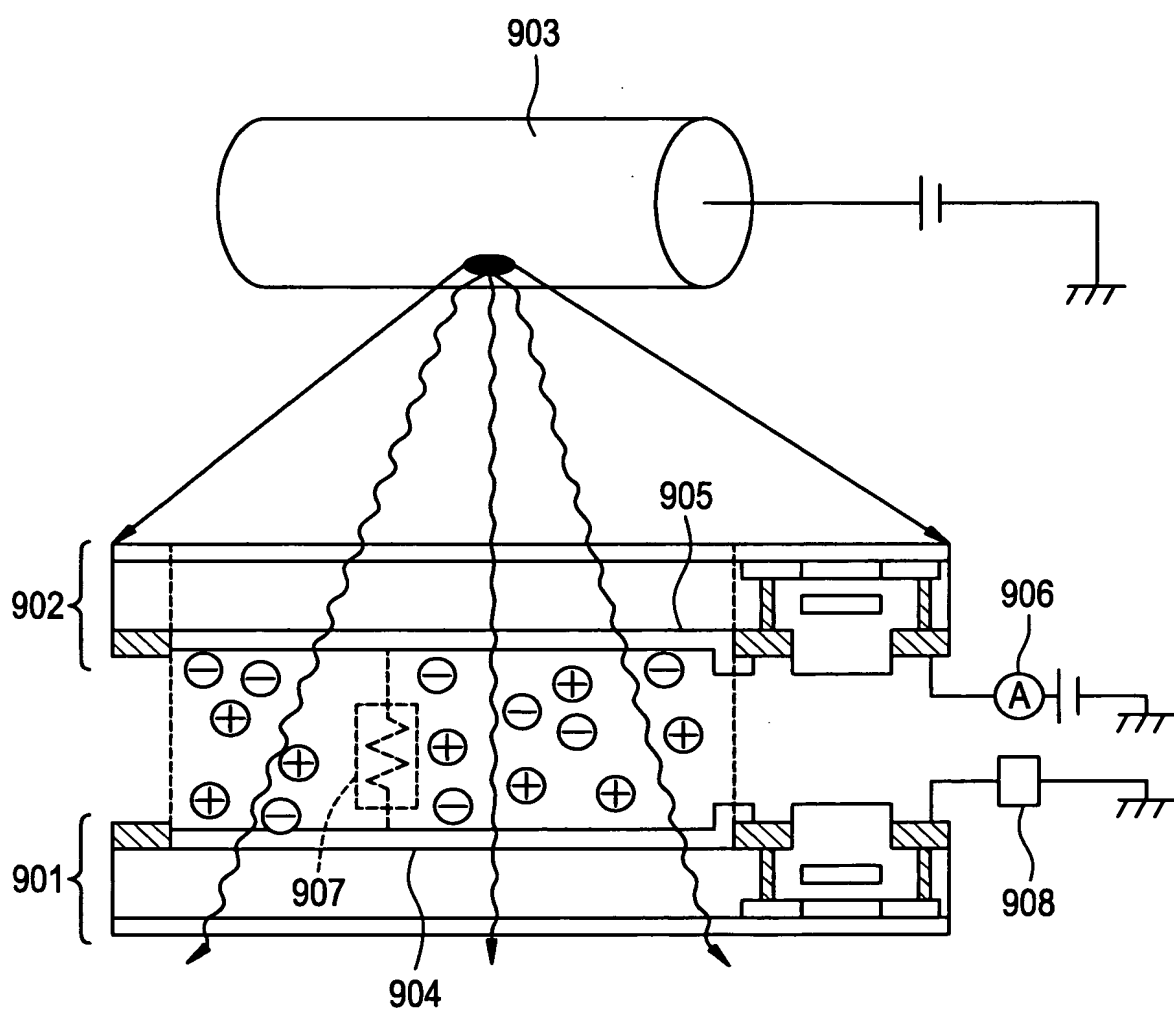


FIG. 10

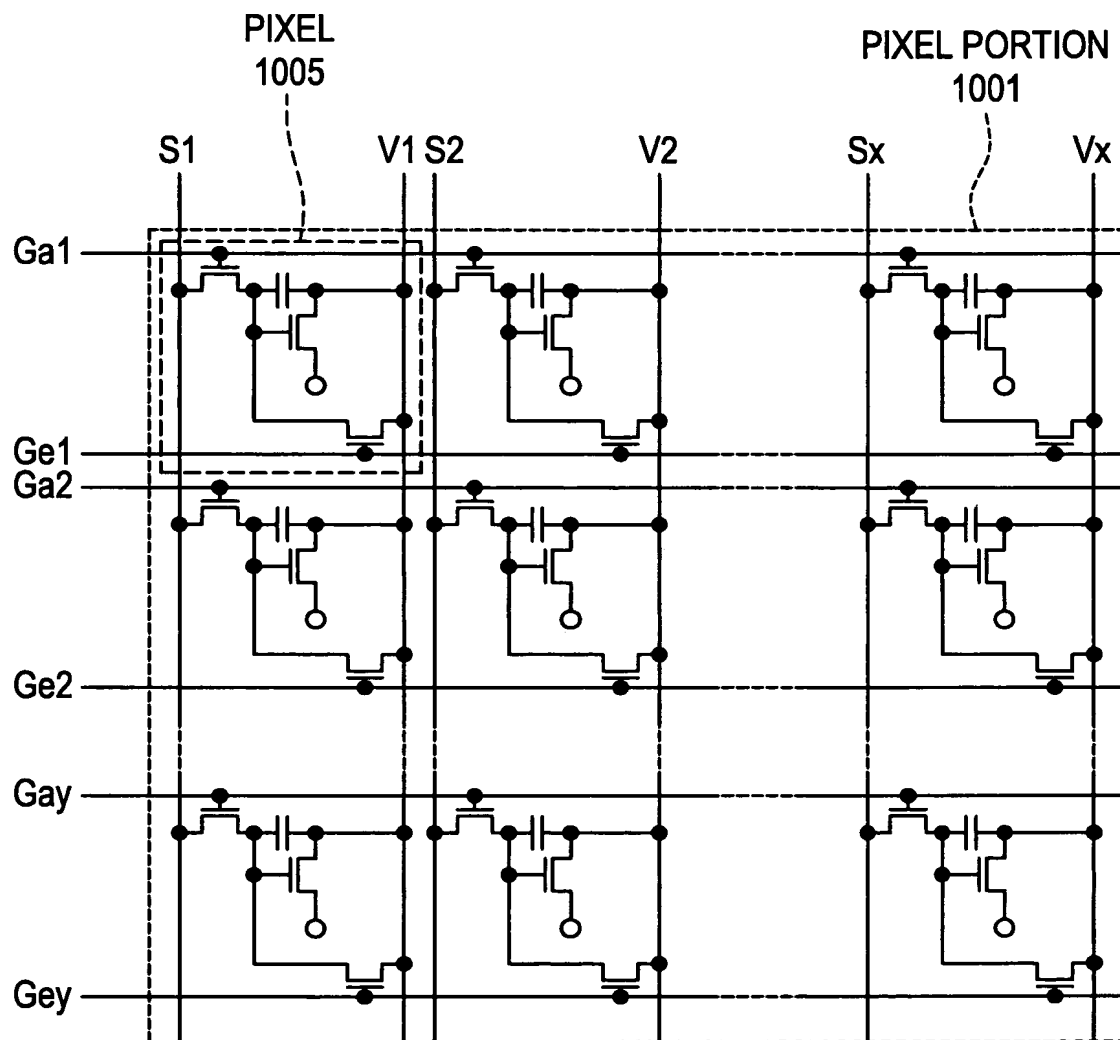


FIG. 11

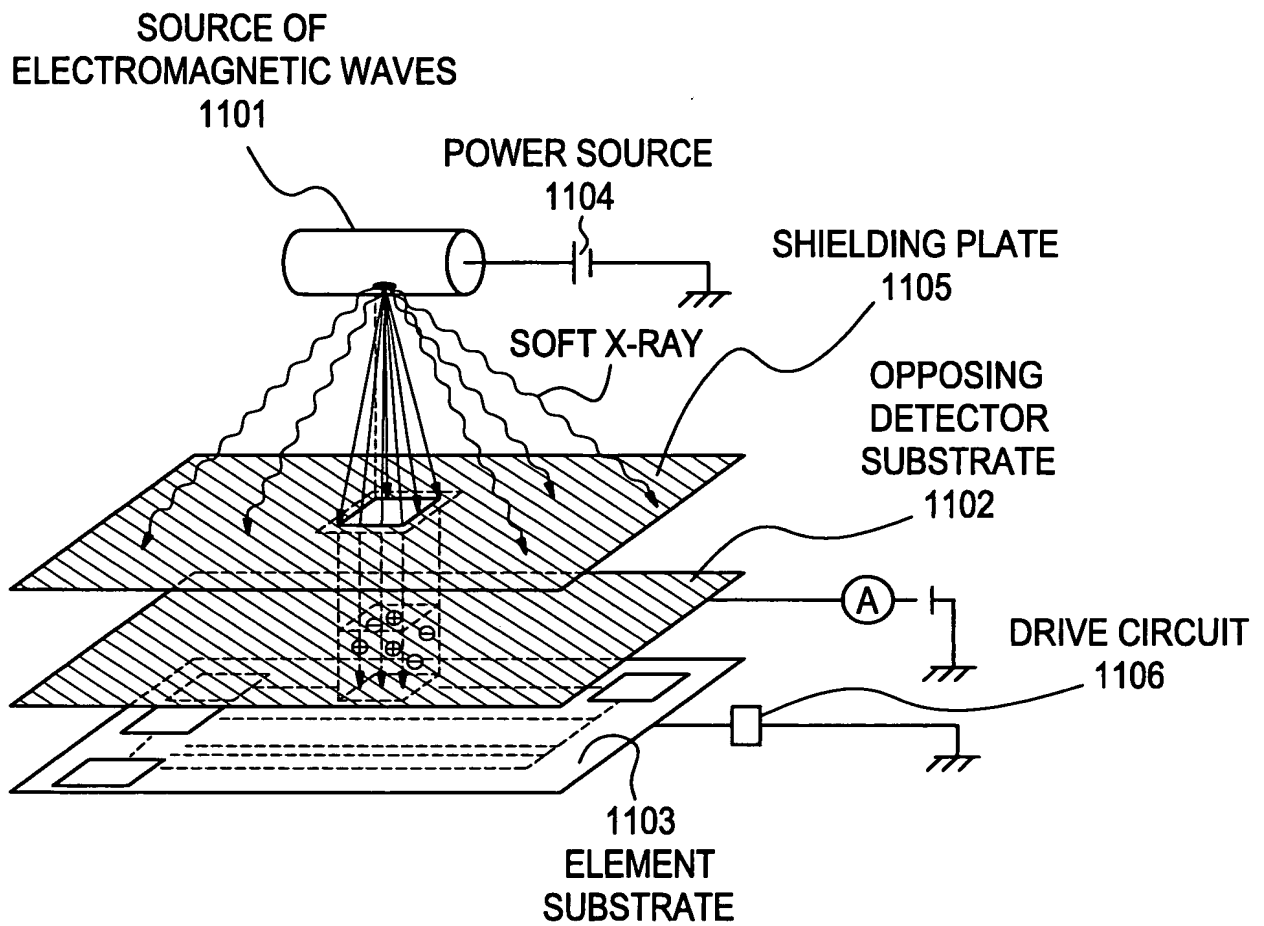


FIG. 12

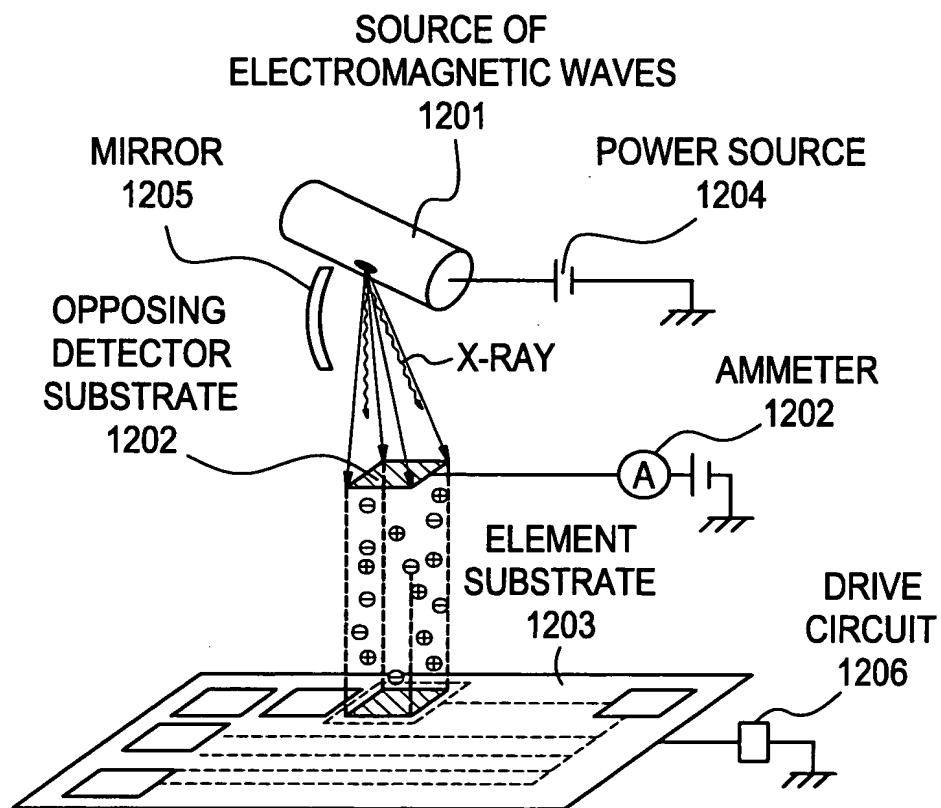


FIG. 13A

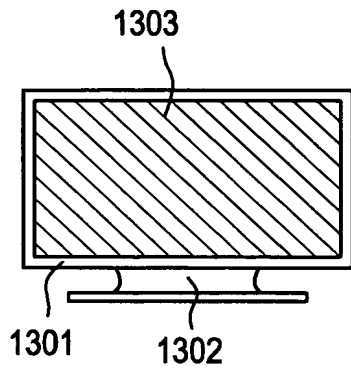


FIG. 13B

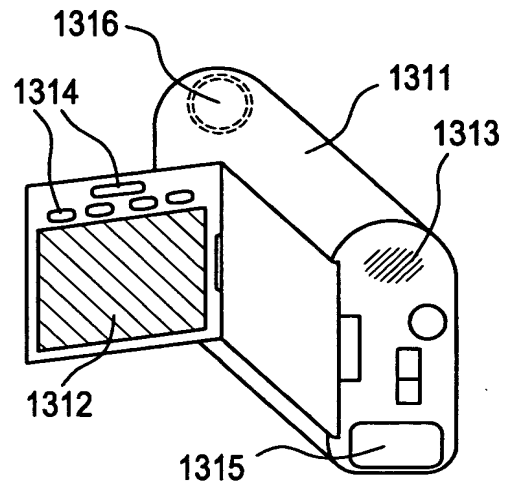


FIG. 13C

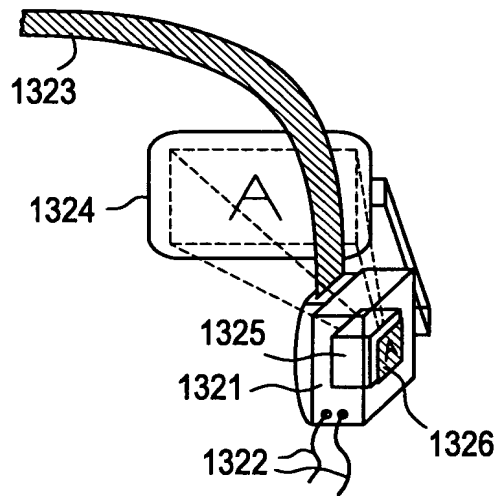


FIG. 13D

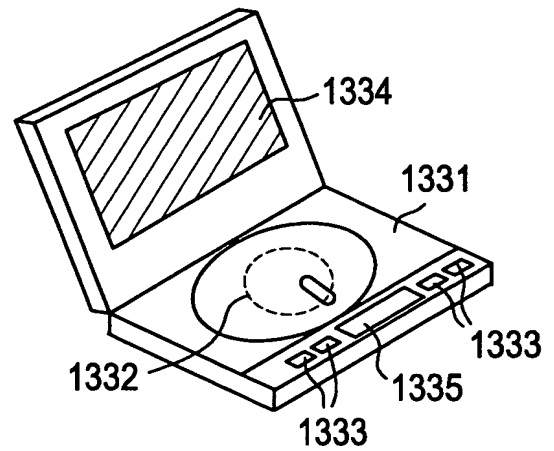


FIG. 13E

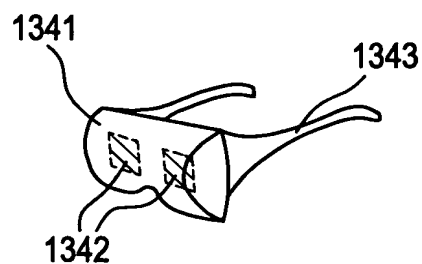
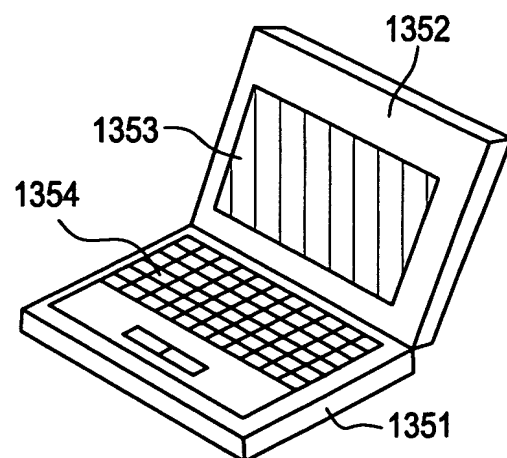


FIG. 13F



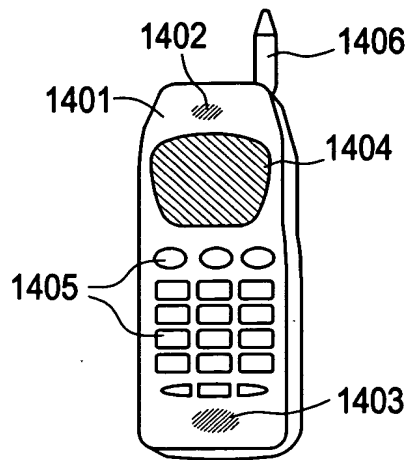
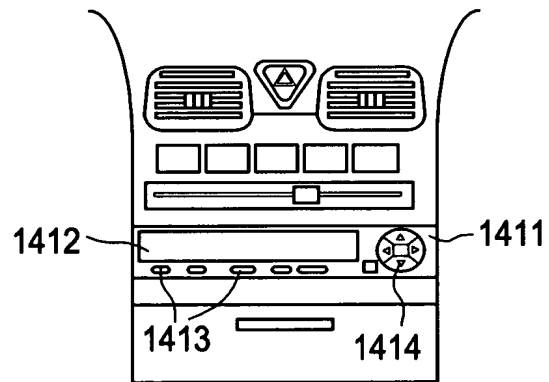
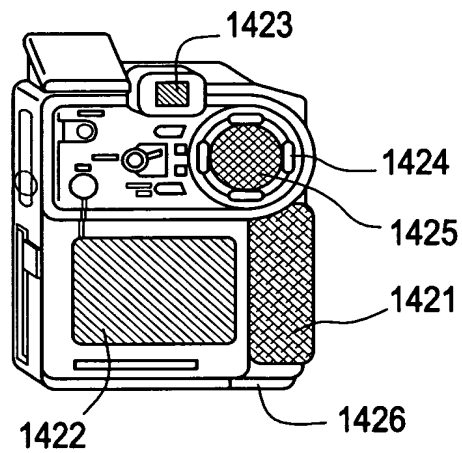
**FIG. 14A****FIG. 14B****FIG. 14C**



FIG. 15

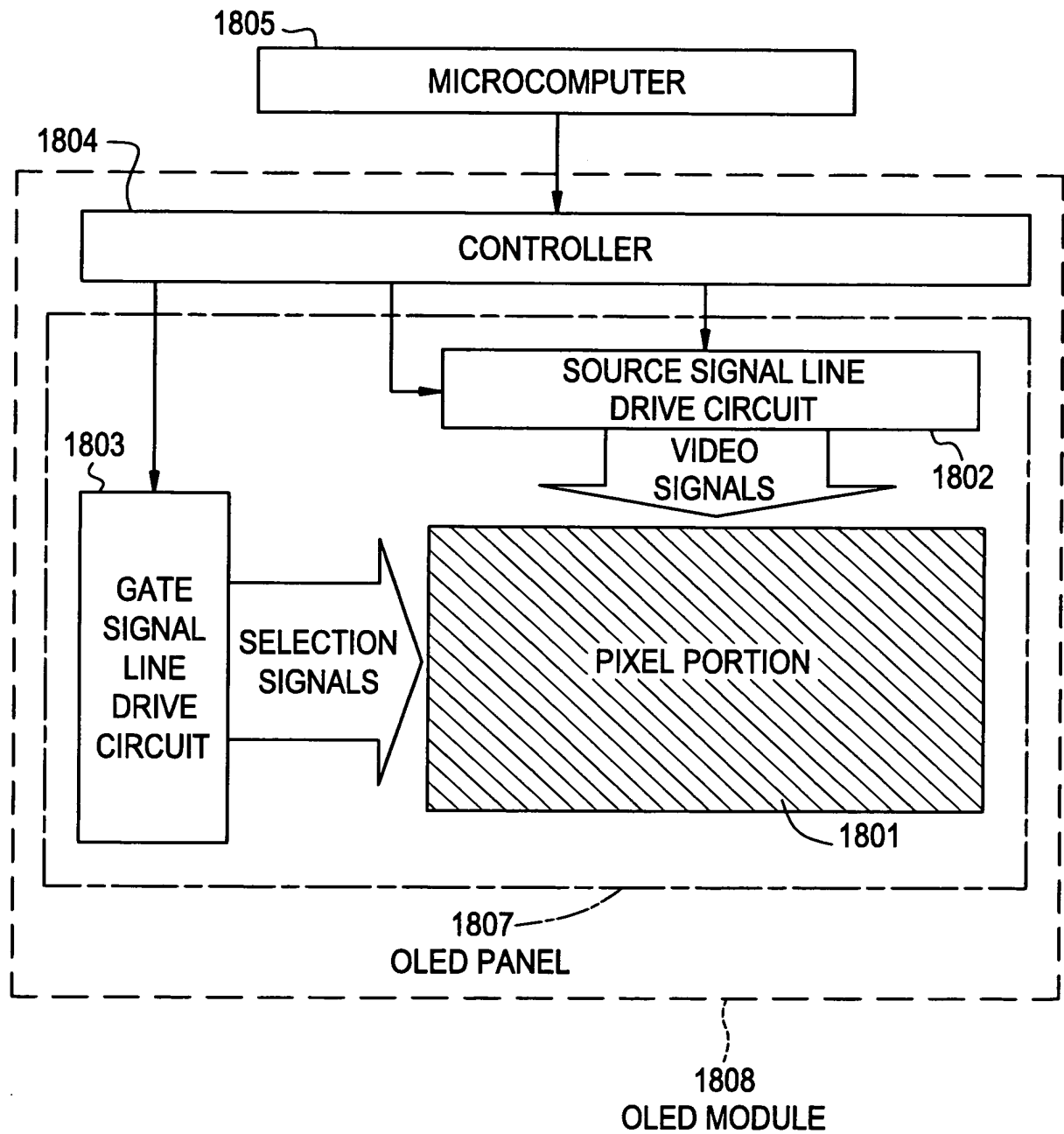


FIG. 16A

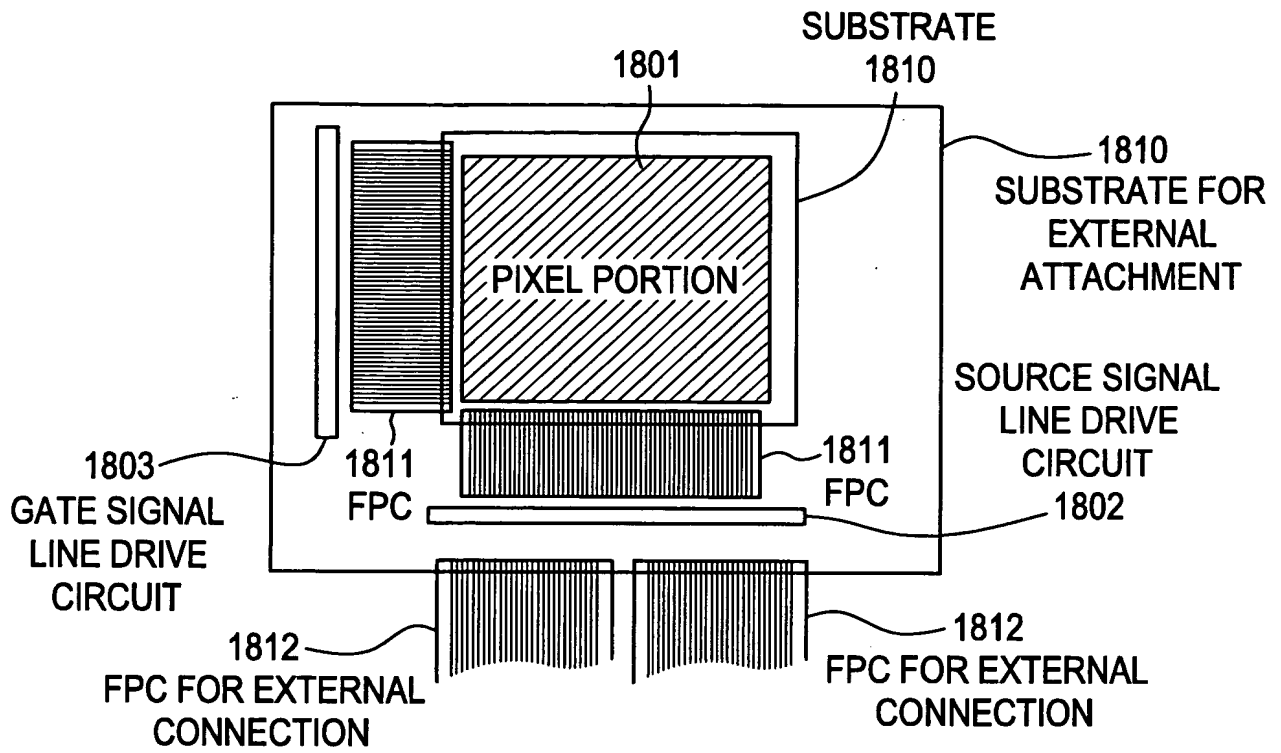


FIG. 16B

